

INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i>	Docket number (Optional) 15436.442.6	Application Number 10/781,446
	Applicant(s) Bo Su Chen	
	Filing Date 02/17/2004	Group Art Unit 2874 2863

* Examiner Initial	OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)
<i>h</i>	Wieder, H. H., "Fermi Level and Surface Barrier of Ga _{1-x} In _x As Alloys," <u>Applied Physics Letters</u> , Vol. 38, No. 3, February 1, 1981, pp. 170-171.
<i>h</i>	Wipiejewski, et al., "VCSELs for Datacom Applications," Invited Paper, Part of the SPIE Conference on Vertical-Cavity Surface-Emitting Lasers III, San Jose, California, SPIE, Vol. 3627, January 1999, pp. 14-22.
<i>h</i>	Y.M. Yang, et al., "Ultralow Threshold Current Vertical Cavity Surface Emitting Lasers Obtained with Selective Oxidation," <u>Electronic Letter</u> , Vol. 31, No. 11, May 25, 1995, pp. 886-888.
<i>h</i>	Yablonovitch, et al., "Photonic Bandgap Structures," <u>J. Opt. Soc. Am. B</u> , Vol. 10, No. 2, February 1993, pp. 283-295.
<i>h</i>	Young, et al., "Enhanced performance of Offset-Gain High Barrier Vertical-Cavity Surface-Emitting Lasers," <u>IEEE J. Quantum Electron.</u> , Vol. 29, No. 6, June 1993, pp. 2013-2022.
<i>h</i>	U.S. Patent Application Serial No. 09/751,422, filed December 29, 2000, entitled "Resonant Reflector for Use with Optoelectronic Devices."
<i>h</i>	U.S. Patent Application Serial No. 09/751,423, filed December 29, 2000, entitled "Spatially Modulated Reflector for an Optoelectronic Device."
<i>h</i>	U.S. Patent Application Publication, Publication No. US 2002/0154675 A1, entitled "Reliability-Enhancing Layers for Vertical Cavity Surface Emitting Lasers," Publication dated October 24, 2002.
<i>h</i>	Athale, et al., "Incoherent Optical Image Processing with Acousto-Optic Pupil-Plane Filtering" <u>Applied Optics</u> , Vol. 34, No. 2, January 10, 1995, pp. 246-280.

EXAMINER <i>Ryan Jg 182</i>	DATE CONSIDERED <i>6/21/05</i>
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.